## Inverse Volcano: A New Molecule–Surface Interaction Phenomenon

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Explosive desorption of guest molecules embedded in amorphous solid water upon its crystallization is known as the "molecular volcano." Here, we describe an abrupt ejection of  $NH<sub>3</sub>$  guest molecules from various molecular host films toward a Ru(0001) substrate upon heating, utilizing both temperature programmed contact potential difference and temperature programmed desorption measurements.  $NH<sub>3</sub>$ molecules abruptly migrate toward the substrate due to either crystallization or desorption of the host molecules, following an "inverse volcano" process considered a highly probable phenomenon for dipolar guest molecules that strongly interact with the substrate.

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Contact potential difference (ΔCPD) studies utilizing an in situ Kelvin probe can be used as a complement to temperature programmed desorption  $(\Delta P$ -TPD) measurements within an ultrahigh vacuum (UHV) environment. In contrast to  $\Delta P$ -TPD studies that track adsorbates as they desorb from a substrate, the noninvasive ΔCPD method is sensitive to the adsorbates' behavior while they are still attached to the substrate. By combining these two methods, an extensive understanding can be obtained about the adsorbate-substrate and adsorbate-adsorbate interactions.

Temperature programmed contact potential difference (TP-ΔCPD) measurements have been employed to study molecular interactions between adsorbates in thin films on a metal substrate [\[1](#page-4-1)–[7\]](#page-4-2), the self-polarization of thick condensed films [[8](#page-4-3)–[10](#page-4-4)], charging of water films [[11](#page-4-5)–[16\]](#page-4-6), and mixing of guest molecules in amorphous solid water (ASW) host films [\[17\]](#page-4-7). Previous studies have shown that there is a good, quantitative correlation between the derivative of the TP- $\Delta$ CPD [d( $\Delta$ CPD)/dT] and  $\Delta P$ -TPD spectra, including surface coverage determination [\[1](#page-4-1)[,6](#page-4-8)]. Using ΔP-TPD methods, an explosive desorption of  $N_2$  molecules caged in ASW [\[18](#page-4-9)] was subsequently coined by Smith et al. as the "molecular volcano." In their case,  $CCl_4$  molecules trapped in ASW are abruptly desorbed to the vacuum, as a result of crystallization of the ASW film [\[19\]](#page-4-10). This phenomenon has since been discussed extensively for various other guest atoms and molecules trapped exclusively in ASW [\[18](#page-4-9)–[24](#page-5-0)]. Recently, it was also reported for methyl chloride molecules caged in amorphous solid ammonia films [\[10\]](#page-4-4).

In this Letter, we describe a new molecule-surface phenomenon in which guest molecules (NH<sub>3</sub>) placed in host films of krypton (Kr), deuterated methyl chloride  $(CD_3Cl)$ , deuterated methanol  $(CD_3OD)$ , and water (ASW) are abruptly ejected toward the Ru(0001) substrate. We coin this effect the "inverse volcano" (IV), relating this phenomenon to the molecular volcano. The IV describes the ejection of guest molecules toward the substrate as structural changes occur in the host film prior to or during desorption as the film is heated.  $NH<sub>3</sub>$  was chosen as the guest molecule because of its strong interaction with the Ru(0001) substrate, while the host film atoms or molecules were chosen to explore the effect of the diverse host film characteristics on the IV phenomenon.

The ejection of  $NH_3$  molecules to the substrate is studied through  $TP-\Delta CPD$  measurements, their derivative profiles  $[d(\Delta CPD)/dT]$ , and  $\Delta P$ -TPD experiments. The experimental setup and methods have been described else-where [[16](#page-4-6),[17](#page-4-7)] and are briefly summarized here. A single crystal Ru(0001) substrate is held at the center of a UHV chamber with a base pressure of  $2 \times 10^{-10}$  Torr, and is cleaned daily by a 15 min 1000 eV  $Ne<sup>+</sup>$  ion sputtering followed by 10 min of annealing at 1450 K. The substrate is exposed to the various gaseous species by backfilling the UHV chamber with the designated gaseous species until the desired film thickness is achieved. The monolayer is determined for each adsorbed species through exposuredependent  $\Delta P$ -TPD experiments. Two monolayers (ML) of NH<sup>3</sup> molecules are placed at different locations within host films of Kr,  $CD_3Cl$ ,  $CD_3OD$ , and  $H_2O$  26 ML thick, grown on the Ru(0001) substrate at 35 K (assuming unity sticking probability). The  $\triangle$ CPD is monitored by a Kelvin probe type S (Besocke Delta-PHI) as adsorption takes place. Once the deposition is complete, the film is heated at a constant rate of 1 K/s while the  $\triangle$ CPD is recorded in a TP-ΔCPD mode. The IV phenomenon is observed in the derivative mode  $\left[\frac{d(\Delta CPD)}{dT}\right]$  as a sharp, negative peak [Fig. [1\(c](#page-1-0))]. A quadrupole mass spectrometer (RGA 200, SRS) is used in separate  $\Delta P$ -TPD measurements to study the desorption of the prepared films.

In Figs. [1\(b\)](#page-1-0) and [1\(c\)](#page-1-0), TP- $\Delta$ CPD and  $d(\Delta$ CPD $)/dT$ spectra for 2 ML of pure  $NH_3$  on Ru(0001) are compared to 2 ML of  $NH_3$  as guest molecules on top of 26 ML thick films of Kr,  $CD_3Cl$ ,  $CD_3OD$ , and under [in direct contact with the Ru(0001) substrate] a 26 ML thick film of  $H_2O$ .

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FIG. 1. (a) Illustrations specifying the locations of 2 ML NH<sub>3</sub> in each host film. (b) TP- $\Delta$ CPD spectra and (c) their derivative  $[d(\Delta CPD)/dT]$  profiles for 2 ML NH<sub>3</sub> on top of 26 ML thick films of Kr (green), CD<sub>3</sub>Cl (purple), CD<sub>3</sub>OD (orange), and under a 26 ML thick film of H<sub>2</sub>O (blue). The films were all adsorbed on a Ru(0001) substrate at 35 K and subsequently heated at a fixed rate of 1 K/s. The negative peak observed in the profiles shown in (c) is referred to as the IV peak. A TP- $\Delta$ CPD profile of clean 2 ML NH<sub>3</sub> on Ru(0001) and its derivative profile  $d(\Delta CPD)/dT$  are shown in red in both (b) and (c) as a reference. The profiles (except that of Kr) are offset for clarity.

Figure [1\(a\)](#page-1-0) contains illustrations to clarify the initial  $NH<sub>3</sub>$ position in each host film. The IV peak is observed in all the respective derivative  $\left[d(\Delta CPD)/dT\right]$  profiles, except in the spectrum of pure  $NH_3$  on Ru(0001). A broad, positive derivative peak is recorded in all the studied films at temperatures where all the host atoms or molecules have already desorbed. This peak is due to the desorbing ammonia molecules following the IV process [see Fig. [1\(c\)](#page-1-0)].

Two conditions must be met for the IV phenomenon to occur: First, the guest molecules should interact more strongly with the substrate than the host molecules interact with the substrate, and second, heating the film should induce a change in the molecular composition (guest vs host molecules) at the surface of the substrate. The nature of the host atoms and molecules and their interaction with  $NH<sub>3</sub>$  affect the temperature at which the IV occurs. In this study, we looked at the effect of inert (Kr), polar (CD<sub>3</sub>Cl), and polar hydrogen bond forming  $(CD_3OD, H_2O)$  host atoms and molecules on the IV of the guest  $NH<sub>3</sub>$  molecules.

It is possible to track these IV molecules upon their arrival at the substrate. When  $2 \text{ ML of NH}_3$  are placed on top of a 26 ML thick Kr film,  $96\%$  of the NH<sub>3</sub> molecules migrate to the substrate upon desorption of the Kr multi-layer at 48 K [Fig. [1\(c\)](#page-1-0) green]. The fraction of  $NH<sub>3</sub>$  molecules ejected toward the substrate is estimated by comparing and calibrating the area under the  $d(\Delta CPD)/dT$ profile for  $NH_3@Kr$  after the IV event to the area obtained this way for 2 ML of clean  $NH_3$  on Ru(0001). In the case of Kr films, there is no crystallization. Therefore, the  $NH<sub>3</sub>$ molecules are ejected toward the substrate simultaneously with the desorption of the multilayer. This leads to a drastic negative change in the  $d(\Delta CPD)/dT$  spectrum at 48 K. In Fig. [2,](#page-2-0) a comparison of the  $d(\Delta CPD)/dT$  spectrum with the  $\Delta P$ -TPD profile tracking  $m/z = 84$  for Kr shows that the peak temperature for the Kr multilayer desorption at 48 K precisely overlaps the IV peak in the  $d(\Delta CPD)/dT$ profile. A redheadlike analysis [[25](#page-5-1)] of the IV spectrum near its peak is used to extract an apparent binding energy of  $12.1 \pm 0.3$  kJ/mol, which is associated with the Kr-NH<sub>3</sub> interaction strength and possibly also reflecting a diffusion barrier of ammonia through the desorbing Kr atoms [[26](#page-5-2)]. In the  $\Delta P$ -TPD profile, a small peak is observed at 56 K, which is attributed to Kr atom monolayer desorption, which occurs at 58 K [\[27\]](#page-5-3). In the  $d(\Delta CPD)/dT$  profile, a peak is observed at 62 K, which corresponds with the completion of desorption of the Kr monolayer, as seen by comparing the  $\Delta P$ -TPD and  $d(\Delta CPD)/dT$  profiles (inset Fig. [2](#page-2-0)). Clean  $NH_3$  molecules eventually desorb from  $Ru(0001)$  in

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FIG. 2. Comparison between  $\Delta P$ -TPD (green) and  $d(\Delta CPD)/dT$  (navy) profiles for 2 ML of NH<sub>3</sub> adsorbed on top of a 26 ML thick film of Kr at 35 K. Inset: enlargement of the temperature range 35–85 K.

a broad, positive  $d(\Delta CPD)/dT$  peak extending up to 350 K [[10](#page-4-4)] [see Fig. [1\(c](#page-1-0)), red].

When 2 ML NH<sub>3</sub> are adsorbed on top of a 26 ML thick host film of  $CD_3Cl$ , 96% of the NH<sub>3</sub> molecules migrate to the substrate upon crystallization of the CD<sub>3</sub>Cl at 76 K, corresponding with an apparent  $NH<sub>3</sub>-CD<sub>3</sub>-Cl$  binding energy (or diffusion barrier) of  $19.2 \pm 0.3$  kJ/mol. In Fig. [3](#page-2-1), a comparison between the  $d(\Delta CPD)/dT$  and  $\Delta P$ -TPD ( $m/z = 53$ ) profiles reveals that the IV peak occurs significantly before the desorption of any  $CD<sub>3</sub>Cl$  is recorded. In contrast to the case of Kr atoms as the host film, it is apparent in the case of  $CD_3Cl$  as the host molecules that the signal observed in the  $d(\Delta CPD)/dT$ spectrum is related to morphological changes taking place inside the film. In an unpublished study from our group, thick films of  $CD_3Cl$  were charged with either Ne<sup>+</sup> ions or low energy electrons and subsequently heated in TP-ΔCPD experiments. The  $d(\Delta CPD)/dT$  profiles of both the negatively and positively charged  $CD_3Cl$  films show a discharge peak at 75 K. This is an indication that a significant morphological change in the film is taking place, which in this case is likely the crystallization of amorphous  $CD<sub>3</sub>Cl$ at 75 K. We could not find previously published work regarding this crystallization temperature under UHV conditions. When crystallization of the  $CD<sub>3</sub>Cl$  film occurs, the  $NH_3$  molecules are ejected toward the  $Ru(0001)$ substrate through cracks formed in the film as a result of the crystallization process. At this temperature, desorption of  $NH_3$  and  $CD_3Cl$  molecules to the vacuum is not observed (Fig. [3\)](#page-2-1). An additional, smaller peak (negative) in the  $d(\Delta CPD)/dT$  profile is observed at 113 K. This may be correlated with the desorption of  $CD<sub>3</sub>Cl$  molecules that became compressed by the migrating  $NH<sub>3</sub>$  molecules on the Ru(0001) substrate or became integrated into the  $NH<sub>3</sub>$ monolayer on the substrate. Both  $CD_3Cl$  and  $NH_3$  molecules display lateral repulsion between neighboring

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FIG. 3. Comparison between  $\Delta P$ -TPD (purple) and  $d(\Delta CPD)/dT$  (navy) profiles for 2 ML of NH<sub>3</sub> adsorbed on top of a 26 ML thick film of  $CD_3Cl$  at 35 K. Inset: enlargement of the temperature range 105–130 K.

molecules while adsorbed at monolayer levels on Ru(0001). Both molecules are adsorbed vertically on the Ru(0001) with the hydrogen and methyl groups facing the vacuum and have similar densities in the first adsorbed layer  $(4.0 \times 10^{14} \text{ NH}_3 \text{ molecules/cm}^2 \text{ vs } 3.6 \times$  $10^{14}$  CH<sub>3</sub> Cl molecules/cm<sup>2</sup>) [\[6](#page-4-8),[28](#page-5-4)[,29\]](#page-5-5). It is possible that after most of the  $CD<sub>3</sub>Cl$  molecules have desorbed, some remain bound to the substrate, surrounded by  $NH<sub>3</sub>$  molecules that have performed the IV process. A previous study has shown that  $NH_3$  molecules compress and cage  $CD_3Cl$ molecules on Ru(0001) [\[10\]](#page-4-4), similar to the  $CD_3Cl@H_2O$ system [[30](#page-5-6)], leading to a lower desorption temperature at the submonolayer. In the  $NH<sub>3</sub>@CD<sub>3</sub>Cl$  case presented here, at the completion of multilayer desorption, the remaining  $CD<sub>3</sub>Cl$  molecules become incorporated into the NH<sub>3</sub> monolayer. As these  $CD<sub>3</sub>Cl$  molecules gradually desorb (at 113 K), the  $NH_3$  molecules begin to find their optimal orientation (vertical) on the substrate, resulting in the negative  $d(\Delta CPD)/dT$  peak at 113 K, and a continued decrease in the  $\triangle$ CPD until the NH<sub>3</sub> molecules begin to desorb [see Figs. [3\(b\)](#page-2-1) and [3\(c\)](#page-2-1)].

Although both  $CD_3OD$  and  $H_2O$  molecules form hydrogen bonds with  $NH_3$  molecules, the behavior of  $NH_3$  as guest molecules in each of these hosts is different. When  $2MLNH<sub>3</sub>$ are placed on top of a  $26 \text{ ML CD}_3$ OD host film, a relatively low intensity IV is observed at 120 K [Fig. [1\(b\)](#page-1-0)], around the crystallization temperature of  $CD<sub>3</sub>OD$  reported in the literature to be 115 K [[31\]](#page-5-7). The extracted apparent binding energy (or diffusion barrier) associated with the  $NH<sub>3</sub>-CD<sub>3</sub>OD$ interaction is  $30.5 \pm 0.5$  kJ/mol. Only 68% of the NH<sub>3</sub> molecules migrate to the substrate. The complicated derivative peak in the case of the  $CD<sub>3</sub>OD$  host film that includes a positive peak near 146 K is due to the desorption of the methanol multilayer at this temperature [\[17](#page-4-7)].

In the case of ASW as the host, in comparison, the IV observed at 165 K is most intense when the 2 ML NH<sub>3</sub> molecules are placed under the 26 ML ASW film, in direct contact with the Ru(0001) substrate and occurs at the multilayer desorption temperature of  $H_2O$  [Fig. [1\(b](#page-1-0))]. The IV is less intense for  $NH_3$  molecules placed on top of an ASW film since most of the  $NH<sub>3</sub>$  molecules desorb to the vacuum before the crystallization temperature of ASW is reached. When NH<sub>3</sub> molecules are adsorbed directly on the clean Ru(0001) substrate, they are displaced at the substrate by incoming  $H_2O$  molecules [[17](#page-4-7)] and remain trapped inside the ASW film until they are attracted down to the substrate upon multilayer desorption of the water molecules at 165 K. The extracted apparent binding energy or diffusion barrier associated with the  $NH<sub>3</sub>-H<sub>2</sub>O$  interaction is  $43.1 \pm 0.5$  kJ/mol. Following the IV event, 84% of the  $NH<sub>3</sub>$  molecules are found at the substrate after all the water molecules have desorbed. These disparities can be explained by the differences in hydrogen bonding propensity of NH<sub>3</sub> with H<sub>2</sub>O and NH<sub>3</sub> with CD<sub>3</sub>OD. Both H<sub>2</sub>O and NH<sup>3</sup> form tetrahedral hydrogen bonded structures, with up to four hydrogen bonds in crystalline ices. In contrast,  $CD<sub>3</sub>OD$  forms only two hydrogen bonds with neighboring molecules  $[32,33]$  $[32,33]$ . This means that NH<sub>3</sub> molecules can more readily incorporate themselves into an  $H_2O$  ice than in a  $CD_3OD$  ice. Therefore, when the  $CD_3OD$  ice crystallizes, the  $NH<sub>3</sub>$  guest molecules are less likely to be incorporated into the ice and are ejected from the film through the cracks that form upon crystallization and are pulled toward the  $Ru(0001)$  substrate. Although  $NH<sub>3</sub>$  is not easily incorporated into  $CD<sub>3</sub>OD$  hydrogen bonding network,  $NH_3$  and  $CD_3OD$  form a strong hydrogen bond, stronger than that of  $NH_3$  and water [\[34\]](#page-5-10). This can hinder the  $NH<sub>3</sub>$  migration to the substrate and can explain why a relatively small amount (68%) of  $NH_3$  molecules are found at the substrate following the IV event, indicating that the rest of the  $NH_3$  molecules desorb with the  $CD_3OD$  multilayer, as revealed by the positive derivative peak  $d(\Delta CPD)/dT$  at 146 K shown in Fig. [1\(c](#page-1-0)).

In the case of  $NH<sub>3</sub>@ASW$ , upon ASW crystallization at 158 K most of the  $NH_3$  molecules are incorporated within the water-ice crystal structure and do not migrate to the substrate until water desorption occurs at 165 K. The somewhat weaker hydrogen bonds and the higher crystallization temperature explain why a larger fraction of the ammonia molecules (compared to methanol as a host) are ejected toward the substrate (84% for the ASW vs 68% in the  $CD_3OD$  case). Ammonia molecules that have not undergone the IV process desorb with the  $H_2O$  or CD<sub>3</sub>OD host molecules.

Several  $\Delta P$ -TPD studies have been conducted to study the site competition between adsorbates on  $TiO<sub>2</sub>$ (110) [[35](#page-5-11)–[37\]](#page-5-12) and forsterite [\[38](#page-5-13)] substrates. Although these are not metallic substrates, these studies nevertheless show that an adsorbate can be displaced at the substrate by subsequently adsorbed adsorbates that are characterized by stronger binding to the substrate. For acetone-water [\[35\]](#page-5-11) and acetone-methanol [[36](#page-5-14)] systems, the water or methanol displacement of acetone occurs before multilayer desorption is observed, but the exact temperature of the displacement was not investigated. Similar observations were reported for the  $CO<sub>2</sub>/H<sub>2</sub>O$  system over the same substrates [\[37](#page-5-12)[,38](#page-5-13)].

The TP-ΔCPD measurements and their derivative profiles  $\left[\frac{d(\Delta CPD)}{dT}\right]$  demonstrate the unique capability to observe in situ structural changes within an adsorbed film (host molecule), as the temperature is being increased. Through these methods, one may determine the temperature at which a displacement at the substrate occurs by associating the peak of the IV with the displacement process. This is under the condition that the molecule that binds more strongly to the substrate (the displacing one) leads to a stronger change in CPD.

Whether the IV occurs upon crystallization or desorption of the host molecular ice is dependent on the nature and strength of interaction between the guest molecules and the host molecules in the film as well as the intermolecular interaction among the host molecules (atoms). When the host atom is inert  $(NH_3@Kr)$  and does not crystallize prior to its desorption, or when the guest molecule is well incorporated into the crystal structure of the host film  $(NH_3@ASW)$ , the IV is observed upon desorption of the host atoms or molecules. When the guest molecules are weakly interacting with the host molecules  $(NH_3@CD_3Cl)$ or have a high energy barrier for incorporation into the crystal structure of the host  $(NH_3@CD_3OD)$ , the IV is observed upon crystallization of the host film. As in the case of the volcano desorption, the crystallization energy apparently propels the guest species' motion toward the substrate [\[19\]](#page-4-10). The IV peak is correlated with apparent binding (or diffusion barrier) energies ranging from 12.1 to 43.1 kJ/mol with the  $NH_3$ -Kr interaction being the weakest and the  $NH<sub>3</sub>-H<sub>2</sub>O$  interaction being the strongest. These values are within  $4 \text{ kJ/mol}$  of the literature values reported for the heat of vaporization of each pure host film [[39](#page-5-15)], suggesting a correlation between the observed apparent binding energies of the guest molecule and the host molecules' interaction among themselves, thereby affecting the temperature at which the guest molecules can undergo the IV process (see Fig. [1](#page-1-0)). The temperatures at which the IV occurs are therefore 48, 76, 120, and 165 K for  $NH<sub>3</sub>/Kr$ ,  $NH<sub>3</sub>/CD<sub>3</sub>Cl$ ,  $NH<sub>3</sub>/CD<sub>3</sub>OD$ , and  $NH<sub>3</sub>/H<sub>2</sub>O$ , respectively. Our extracted binding strength of  $NH_3$  to the Ru(0001) is significantly stronger than the intermolecular attraction energy of  $NH<sub>3</sub>$  to any of the host molecules, characterized by 77.3 kJ/mol at a coverage of about 0.2 ML (lateral repulsion leads to a broad desorption peak).

To summarize, we have demonstrated a new molecule– surface interaction phenomenon, IV, in which guest molecules may be abruptly propelled toward the substrate and not just to the vacuum via the molecular volcano process that has been extensively discussed since 1997 [[19\]](#page-4-10). The direction of migration depends primarily on the nature of the guest molecule–substrate interaction strength vs the host molecules intermolecular interactions. In cases where the guest molecule binds less strongly to the substrate than the host molecule, the IV is not observed, as in the case of the  $CD_3Cl@ASW$  system (not shown). The occurrence of the molecular and inverse volcanos can be considered as mutually exclusive. The fraction of the  $NH<sub>3</sub>$  guest molecules found at the ruthenium surface following the host molecules' complete desorption is 68%–96% of the initial 2  $ML NH<sub>3</sub>$  for the systems studied here, as determined by ΔCPD methods following calibration against clean ammonia desorption, as detected by the  $\left[d(\Delta CPD)/dT\right]$  analysis. Fewer  $NH<sub>3</sub>$  molecules were ejected toward the substrate via the IV process when the interaction between the guest and host molecules was stronger.

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M. S. A. performed all the experiments and data analysis and wrote the manuscript. R. S. has participated in some of the analysis and is responsible for all the LabView algorithms. M. A. wrote the manuscript and is responsible for the entire study.

The authors declare no conflicts of interest.

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- <span id="page-4-1"></span>[1] H. Pfnür, P. Feulner, and D. Menzel, The influence of adsorbate interactions on kinetics and equilibrium for CO on Ru(001). II. Desorption kinetics and equilibrium, [J. Chem.](https://doi.org/10.1063/1.445571) Phys. 79[, 12 \(1983\)](https://doi.org/10.1063/1.445571).
- [2] J. Kołaczkiewicz and E. Bauer, Temperature Dependence of the Work Function of Adsorbate-Covered Metal Surfaces: A New Method for the Study of Two-Dimensional Phase Transitions, [Phys. Rev. Lett.](https://doi.org/10.1103/PhysRevLett.53.485) 53, 485 (1984).
- [3] P. Feulner and D. Menzel, The adsorption of hydrogen on ruthenium(001): Adsorption states, dipole moments and kinetics of adsorption and desorption, [Surf. Sci.](https://doi.org/10.1016/0039-6028(85)90045-7) 154, 465 [\(1985\).](https://doi.org/10.1016/0039-6028(85)90045-7)
- [4] K. L. Kostov, H. Rauscher, and D. Menzel, Adsorption of CO on oxygen-covered Ru(001), Surf. Sci. 278[, 62 \(1992\).](https://doi.org/10.1016/0039-6028(92)90584-S)
- <span id="page-4-8"></span>[5] T. Livneh and M. Asscher, Work function study of the adsorption, lateral repulsion, and fragmentation of  $CH<sub>3</sub>Br$ on Ru(001), [J. Phys. Chem. B](https://doi.org/10.1021/jp971134a) 101, 7505 (1997).
- [6] T. Livneh, Y. Lilach, and M. Asscher, Dipole–dipole interactions among  $CH<sub>3</sub>Cl$  molecules on Ru(001): Correlation between work function change and thermal desorption studies, J. Chem. Phys. 111[, 11138 \(1999\).](https://doi.org/10.1063/1.480496)
- <span id="page-4-2"></span>[7] T. Livneh and M. Asscher, The adsorption and decomposition of  $C_2H_4$  on Ru(001): A combined TPR and work function change study, [J. Phys. Chem. B](https://doi.org/10.1021/jp000272o) 104, 3355 (2000).
- <span id="page-4-3"></span>[8] I. K. Gavra, A. N. Pilidi, and A. A. Tsekouras, Spontaneous polarization of vapor-deposited 1-butanol films and its dependence on temperature, [J. Chem. Phys.](https://doi.org/10.1063/1.4978239) 146, 104701 [\(2017\).](https://doi.org/10.1063/1.4978239)
- [9] R. Sagi, M. Akerman, S. Ramakrishnan, and M. Asscher, The role of thermal history on spontaneous polarization and phase transitions of amorphous solid water films studied by contact potential difference measurements, [J. Chem. Phys.](https://doi.org/10.1063/5.0017712) 153[, 144702 \(2020\).](https://doi.org/10.1063/5.0017712)
- <span id="page-4-4"></span>[10] R. Sagi, M. Akerman, S. Ramakrishnan, and M. Asscher, Spontaneous polarization of thick solid ammonia films, J. Chem. Phys. 153[, 124707 \(2020\)](https://doi.org/10.1063/5.0017853).
- <span id="page-4-5"></span>[11] A. A. Tsekouras, M. J. Iedema, and J. P. Cowin, Amorphous Water-Ice Relaxations Measured with Soft-Landed Ions, [Phys. Rev. Lett.](https://doi.org/10.1103/PhysRevLett.80.5798) 80, 5798 (1998).
- [12] Y. Horowitz and M. Asscher, Low energy charged particles interacting with amorphous solid water layers, [J. Chem.](https://doi.org/10.1063/1.3697870) Phys. 136[, 134701 \(2012\).](https://doi.org/10.1063/1.3697870)
- [13] J. Shi, M. Famá, B.D. Teolis, and R.A. Baragiola, Ioninduced electrostatic charging of ice at 15–160 K, [Phys.](https://doi.org/10.1103/PhysRevB.85.035424) Rev. B 85[, 035424 \(2012\).](https://doi.org/10.1103/PhysRevB.85.035424)
- [14] S. Shin, Y. Kim, E. Moon, D. H. Lee, H. Kang, and H. Kang, Generation of strong electric fields in an ice film capacitor, J. Chem. Phys. 139[, 074201 \(2013\)](https://doi.org/10.1063/1.4818535).
- [15] R. Sagi, M. Akerman, S. Ramakrishnan, and M. Asscher, Temperature effect on transport, charging, and binding of low-energy electrons interacting with amorphous solid water films, [J. Phys. Chem. C](https://doi.org/10.1021/acs.jpcc.8b01674) 122, 9985 (2018).
- <span id="page-4-6"></span>[16] M. Akerman, R. Sagi, and M. Asscher, Charging amorphous solid water films by  $Ne<sup>+</sup>$  ions characterized by contact potential difference measurements, [J. Phys. Chem. C](https://doi.org/10.1021/acs.jpcc.0c07969) 124, [23270 \(2020\).](https://doi.org/10.1021/acs.jpcc.0c07969)
- <span id="page-4-7"></span>[17] M. Akerman, R. Sagi, and M. Asscher, Low-temperature mixing of polar hydrogen bond-forming molecules in amorphous solid water, [J. Phys. Chem. C](https://doi.org/10.1021/acs.jpcc.2c00877) 126, 6825 [\(2022\).](https://doi.org/10.1021/acs.jpcc.2c00877)
- <span id="page-4-9"></span>[18] T. Livneh, L. Romm, and M. Asscher, Cage formation of  $N_2$ under  $H_2O$  overlayer on Ru(001), [Surf. Sci.](https://doi.org/10.1016/0039-6028(95)01370-9) 351, 250 [\(1996\).](https://doi.org/10.1016/0039-6028(95)01370-9)
- <span id="page-4-10"></span>[19] R. S. Smith, C. Huang, E. K. L. Wong, and B. D. Kay, The Molecular Volcano: Abrupt CCl<sub>4</sub> Desorption Driven by the Crystallization of Amorphous Solid Water, [Phys. Rev. Lett.](https://doi.org/10.1103/PhysRevLett.79.909) 79[, 909 \(1997\).](https://doi.org/10.1103/PhysRevLett.79.909)
- [20] R. A. May, R. S. Smith, and B. D. Kay, The molecular volcano revisited: Determination of crack propagation and distribution during the crystallization of nanoscale amorphous solid water films, [J. Phys. Chem. Lett.](https://doi.org/10.1021/jz201648g) 3, 327 [\(2012\).](https://doi.org/10.1021/jz201648g)
- [21] R. A. May, R. S. Smith, and B. D. Kay, The release of trapped gases from amorphous solid water films. I. "Top-down" crystallization-induced crack propagation probed using the molecular volcano, [J. Chem. Phys.](https://doi.org/10.1063/1.4793311) 138, [104501 \(2013\).](https://doi.org/10.1063/1.4793311)
- [22] R. Alan May, R. Scott Smith, and B. D. Kay, The release of trapped gases from amorphous solid water films. II. "Bottom-up" induced desorption pathways, [J. Chem. Phys.](https://doi.org/10.1063/1.4793312) 138[, 104502 \(2013\).](https://doi.org/10.1063/1.4793312)
- [23] R. Souda, Hydration of ammonia, methylamine, and methanol in amorphous solid water, [Chem. Phys. Lett.](https://doi.org/10.1016/j.cplett.2015.12.028) 645[, 27 \(2016\).](https://doi.org/10.1016/j.cplett.2015.12.028)
- <span id="page-5-0"></span>[24] R. Souda, Hydration–dehydration of acetonitrile and methanol in amorphous solid water, [J. Phys. Chem. C](https://doi.org/10.1021/acs.jpcc.5b05737) 120, 934 [\(2016\).](https://doi.org/10.1021/acs.jpcc.5b05737)
- <span id="page-5-1"></span>[25] J. T. Yates, Experimental Innovations in Surface Science: A Guide to Practical Laboratory Methods and Instruments (Springer-Verlag, New York, 1998).
- <span id="page-5-2"></span>[26] V. N. Antonov, J. S. Palmer, P. S. Waggoner, A. S. Bhatti, and J. H. Weaver, Nanoparticle diffusion on desorbing solids: The role of elementary excitations in bufferlayer-assisted growth, [Phys. Rev. B](https://doi.org/10.1103/PhysRevB.70.045406) 70, 045406 [\(2004\).](https://doi.org/10.1103/PhysRevB.70.045406)
- <span id="page-5-3"></span>[27] H. Schlichting and D. Menzel, Techniques for attainment, control, and calibration of cryogenic temperatures at small single-crystal samples under ultrahigh vacuum, [Rev. Sci.](https://doi.org/10.1063/1.1143992) Instrum. 64[, 2013 \(1993\)](https://doi.org/10.1063/1.1143992).
- <span id="page-5-4"></span>[28] T. Livneh and M. Asscher, The chemistry of  $CH<sub>3</sub>Cl$  and CH3Br on Ru(001), Langmuir 14[, 1348 \(1998\).](https://doi.org/10.1021/la970712b)
- <span id="page-5-5"></span>[29] C. Benndorf and T. E. Madey, Adsorption and orientation of NH<sub>3</sub> on Ru(001), Surf. Sci. 135[, 164 \(1983\).](https://doi.org/10.1016/0039-6028(83)90217-0)
- <span id="page-5-6"></span>[30] Y. Lilach and M. Asscher, Compression and caging of CD<sub>3</sub>Cl by H<sub>2</sub>O layers on Ru(001), [J. Chem. Phys.](https://doi.org/10.1063/1.1505858)  $117,6730$ [\(2002\).](https://doi.org/10.1063/1.1505858)
- <span id="page-5-7"></span>[31] J. Matthiesen, R. S. Smith, and B. D. Kay, Using Rare Gas Permeation to Probe Methanol Diffusion near the Glass Transition Temperature, [Phys. Rev. Lett.](https://doi.org/10.1103/PhysRevLett.103.245902) 103, [245902 \(2009\).](https://doi.org/10.1103/PhysRevLett.103.245902)
- <span id="page-5-8"></span>[32] K. J. Tauer and W. N. Lipscomb, On the crystal structures, residual entropy and dielectric anomaly of methanol, [Acta](https://doi.org/10.1107/S0365110X52001696) Crystallogr. 5[, 606 \(1952\)](https://doi.org/10.1107/S0365110X52001696).
- <span id="page-5-9"></span>[33] B. H. Torrie, S.-X. Weng, and B. M. Powell, Structure of the  $\alpha$ -phase of solid methanol, Mol. Phys. 67[, 575 \(1989\).](https://doi.org/10.1080/00268978900101291)
- <span id="page-5-10"></span>[34] A. D. Fortes, I. G. Wood, and K. S. Knight, The crystal structure of perdeuterated methanol monoammoniate  $(CD_3OD \cdot ND_3)$  determined from neutron powder diffraction data at 4.2 and 180 K, [J. Appl. Crystallogr.](https://doi.org/10.1107/S0021889809035705) 42, 1054 [\(2009\).](https://doi.org/10.1107/S0021889809035705)
- <span id="page-5-11"></span>[35] M.A. Henderson, Acetone and water on  $TiO<sub>2</sub>$  (110): Competition for sites, Langmuir 21[, 3443 \(2005\)](https://doi.org/10.1021/la0476579).
- <span id="page-5-14"></span>[36] M. Shen and M.A. Henderson, Site competition during coadsorption of acetone with methanol and water on  $TiO<sub>2</sub>$ (110), Langmuir 27[, 9430 \(2011\)](https://doi.org/10.1021/la2016726).
- <span id="page-5-12"></span>[37] R. S. Smith, Z. Li, L. Chen, Z. Dohnálek, and B. D. Kay, Adsorption, desorption, and displacement kinetics of  $H_2O$ and  $CO_2$  on TiO<sub>2</sub> (110), [J. Phys. Chem. B](https://doi.org/10.1021/jp501131v) 118, 8054 (2014).
- <span id="page-5-13"></span>[38] R. S. Smith, Z. Li, Z. Dohnálek, and B. D. Kay, Adsorption, desorption, and displacement kinetics of  $H_2O$  and  $CO_2$  on forsterite,  $Mg_2SiO_4$  (011), [J. Phys. Chem. C](https://doi.org/10.1021/jp504187y) 118, 29091 [\(2014\).](https://doi.org/10.1021/jp504187y)
- <span id="page-5-15"></span>[39] Molar enthalpy of vaporization at the boiling point and at 25° C in CRC Handbook of Chemistry and Physics, 103rd ed., edited by J. R. Rumble (CRC Press/Taylor & Francis, 2022).